

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant:

Linyong Pang and Fang-Cheng Chang

Assignee:

Synopsys, Inc.

Title:

SYSTEM AND METHOD FOR PROVIDING DEFECT

PRINTABILITY ANALYSIS OF PHOTOLITHOGRAPHIC MASKS

WITH JOB-BASED AUTOMATION

Serial No.: 10/618,816

File Date: July 11, 2003

Examiner: Vuthe Siek

Art Unit: 2825

Docket No.: NTI-703-1P1P

Date: December 23, 2005

Mail Stop Amendment Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

AMENDMENT IN RESPONSE TO THE SECOND OFFICE ACTION

Initial Comments

Claims 1-3, 5, 7, 9-24, 26, 28, 30-43, and 46-49 are pending in the present application. Claims 1, 4-5, 6-8, 10-16, 20-23, 25-29, 31-36, 41-43, and 45-49 are rejected under 35 USC 102(a/e) as being anticipated by US Patent 6513151 (Erhardt). Claims 9 and 30 are rejected under 35 USC 103(a) as being obvious over Erhardt in view of US Patent 6526164 (Mansfield). Claims 2-5, 19, 24-26, 39, 41-42, 44-45 are rejected under 35 USC 103(a) as being obvious over Erhardt in view of Avant!...Solutions & Products, "Taurus-Lithography 2/22/01, pp. 1-3 (Avant!) or

www.sematech.org/resources/litho/meetings/mask/200107/ODATA-

FORMAT-B03.PDF (Sematch). Claims 16-18 and 36-38 are rejected under 35 USC 103(a) as being obvious over Erhardt in view of US Patent 6498867 (Potucek).

Claims 4, 6, 8, 25, 27, 29, and 45 are cancelled, thereby rendering the rejection of those claims moot. Claims 5, 7, 9, 26, 28, and 30 are amended herein to correct for claim dependency based on the above claim cancellations. Claims 1, 23, and 43 are also amended herein.